A1 [Plasma Materials and Processing]

A1-1-I1 Makoto Kambara	University of Osaka	Mesoplasma rejuvenation of waste powders for a novel recirculation loop in advanced additive manufacturing
A1-1-I2 Hiroshi Furuta	Kochi University of Technology	Shape Control of Carbon Nanotube Forests via Bottom-up Process of Catalyst Nanoparticles
A1-1-I3 Hiroharu Kawasaki	National Institute of Technology (KOSEN), Sasebo College	Trial of elemental gradient functional thin films preparation by sputtering with mixed powder targets III
A1-1-I4 Tamiko Ohshima	Nagasaki University	Single cathode combinatorial deposition using powder target by sputtering process
A1-1-I5 Giichiro Uchida	Meijo University	Fabrication of nanowire film in the plasma sputtering process for Li-ion-battery anode
A1-1-I6 Osamu Sakai	The University of Shiga Prefecture	Complex network in low-temperature plasma analyzed by Shannon entropy
A1-1-I7 Mineo Hiramatsu	Meijo University	Plasma synthesis of 3-dimensional graphene-based materials
A1-1-I8 Masanori Shinohara	Fukuoka University	Graphene growth with high power pulsed plasma
A1-1-I9 Karol Hensel	Comenius University Bratislava	Effect of pellet catalyst properties on gas cleaning process
A1-1-O1 Arunsinh Bakulsinh Zala	Nanyang Technological University	α-Alumina Synthesis at Room Temperature Using a Plasma Focus Device for Fusion Blankets
A1-1-O2 Yanhong Guan	Institute Of Plasma Physics Chinese Academy Of Sciences	Development of boron-coated full-metal wall in EAST for ITER new baseline
A1-2-I1 Shahid Rafique	University of Engineering and Technology, Lahore	Material Fabrication/ Modification using Atmospheric Pressure Plasmas
A1-2-I2 Kosuke Takenaka	Osaka University	Enhancement of bonding strength of metals /organic materials direct bonding vis non-equilibrium atmospheric pressure plasma irradiation
A1-2-I3 Naoki Shirai	Hokkaido University	Self-organized luminescent patterns observed in direct current glow discharge from low pressure to atmospheric pressure
A1-2-I4 Ruixue Wang	Beijing University of Chemical Technology	Atmospheric-Pressure Low-Temperature Plasma for Thin Film Deposition on Metallic Substrates
A1-2-I5 Tatsuru Shirafuji	Osaka Metropolitan University	Surface-Launched Plasma Bullet and Its Application
A1-2-I6 Chuansheng Zhang	Institute of Electrical Engineering, Chinese Academy of Sciences	Improving high-temperature capacitive energy storage of biaxially oriented polypropylene using atmospheric pressure plasma jet
A1-2-I7 Wenjun Ning	Sichuan University	Atmospheric Pressure Plasma Jet: The free jet and its interacting with surfaces
A1-3-I1 Shazia Bashir	Government College Women University Sialkot	Laser -induced plasma as a reliable and versatile tool for material processing
A1-3-I2 Naoto Yamashita	Kyushu University	Large area fabrication of electrically switchable magnetic garnet using a plasma process
A1-3-I3 Naho Itagaki	Kyushu University	Nucleation-Controlled Sputtering Growth of Epitaxial and Non-Epitaxial Oxide Semiconducting Thin Films
A1-3-I4 Heeyeop CHAE	Sungkyunkwan University	Plasma Atomic Layer Etching of Metals and Dielectric Materials
A1-3-I5 Min-Kyu Son	Korea Institute of Ceramic Engineering & Technology	Defect engineering via electron beam annealing treatment for the enhanced activity of electrochemical reactions
A1-3-I6 Kwang-Ryeol Lee	Korea Institute of Science and Technology	Plasma application for manipulating surface properties by diamond-like carbon coatings and surface modification
A1-3-O1 Erik V JOHNSON	LPICM, CNRS, Ecole Polytechnique, Institut Polytechnique de Paris	Etching Uniformity and Profile Control in Patterned Plasma System for HJT-IBC Solar Cell Fabrication
A1-3-O2 Yuan-Ming Chang	Feng Chia University	Residual Stress and Related Properties of TiO2/TiN/TiC Thin Films Deposited by Ion Energy Modulated ALIS and Magnetron Sputtering Hybrid Process
A1-4-I1 Shota Nunomura	National Institute of Advanced Industrial Science and Technology	Radical, ion, and photon's effects on material damage/defects during plasma etching
A1-4-I2 Keiichiro Urabe	Kyoto University	Monitoring of low-temperature plasma processes by in-situ impedance spectroscopy
A1-4-I3 Takayoshi Tsutsumi	Nagoya University	Transport mechanism of active species in high-aspect-ratio hole during plasma etching
A1-4-I4 Hamid Latif	Forman Christian College, Lahore	Effect of Fluorine-Doped Tin Oxide Target Morphology on Thin Film Deposition by Laser Induced Plasma for Perovskite Solar Cell application.
A1-4-I5 Kentaro Tomita	Hokkaido University	Studies of EUV light source plasmas based on measurements of electron temperature and electron density
A1-4-I6 Qing Xiong	Xi'an Jiaotong University	High frequency generation mechanism of DC arc and its detection approach
A1-4-I7 Sarveshwar Sharma	Institute for Plasma Research	Impact of Electron Bounce-Cyclotron Resonance (ECBR) on Plasma Dynamics in Weakly Magnetized Capacitive Discharges
A1-5-I1 Toru Sasaki	Nagaoka University of Technology	Curing Process of Electrically Conductive Adhesives and Formation of Resistant Coatings using Atmospheric Pressure Plasma
A1-5-I2 Matteo Gherardi	Alma Mater Studiorum – Università di Bologna	Atmospheric pressure plasma polymerization with aerosolized precursors
A1-5-I3 Deepak Prasad Subedi	Kathmandu University	Dielectric Barrier Discharge and its Application for Surface Treatment of Materials
A1-5-I4 Takayuki Watanabe	Kyushu University	Multiphase AC arc, fundamentals and applications
A1-5-I5 Nan Jiang	Dalian University of Technology	The Characteristics of Rotating Dielectric Barrier Discharge and Its Modification Effects of Epoxy Resin/Aluminum Nitride (EP/AlN) Composites
A1-5-I6 Haw Jiunn Woo	Universiti Malaya	LOW POWER 50 HZ ARGON GLOW DISCHARGE FOR SURFACE MODIFICATION OF POLYSTYRENE AND POLYTETRAFLUOROETHYLENE
A1-5-I7 Hui Jiang	Chongqing University	Developments and Interactions of the Channels in Surface Dielectric Barrier Discharge
A1-5-O1 Pradeep Lamichhane	University of warwick	NO_x Production in a Stagnant Liquid Layer Using Combined Submerged Plasma Micro-Jets: Synergistic Effects of Jet Dynamics and Catalysts
A1-6-I1 Kai Zhao	Dalian University of Technology	Charged particle dynamics and electron power absorption mode in capacitively coupled argon discharges with different biasing parameters
A1-6-I2 Bocong Zheng	Beijing Institute of Technology	Transport analysis in capacitively coupled plasmas
A1-6-I3 Masaya Shigeta	Tohoku University	The Difficulty and Charm of Computational Plasma Fluid Mechanics
A1-6-I4 Ho Jun Kim	Hanyang University	Analysis of stagnation point flow within an inductively coupled plasma reactor for the enhancement of deposition methodologies
A1-6-I5 Sanghoo Park	KAIST	Practical issues in tomographic reconstruction of semiconductor processing plasmas
A1-6-I6 Haruka Suzuki	Nagoya University	Reconstruction of three-dimensional structure of plasma emission using multi-view images
A1-6-I7 Xuekai Pei	Wuhan University	NO Formation Dynamics in Air Plasma: Advanced Laser Diagnostics
A1-7-I1 Sirui Li	Eindhoven University of TEchnology	Integrated Process for Carbon Valorization Using Plasma-Sorbent Systems
A1-7-I2 Susumu Toko	University of Osaka	Sorption enhanced methanation with plasma catalysis using various types of zeolites
A1-7-I3 Liguang Dou	Institute of Electrical Engineering, Chinese Academy of Sciences	Synergistic promotion of vibrant H radicals and targeted Cu/MgAlO interface for CO2 hydrogenation by non-thermal plasma
A1-7-I4 De-Zheng Yang	Dalian University of Technology	High efficiency NOx synthesis and regulation using dielectric barrier discharge in the needle array packed bed reactor
A1-7-I5 Oi Lun Helena Li	Pusan National University	New era of plasma engineering for catalytic materials synthesis and their applications
A1-7-I6 Dengke Xi	Institute of Electrical Engineering, Chinese Academy of Sciences	Plasma-enabled methane conversion to hydrogen and nanocarbon materials
A1-7-O1 Monika Verma	DELHI TECHNOLOGICAL UNIVERSITY	Effect of Plasma Process Parameters on the Electrical Characteristics of Dual-Gate Graphene Field-Effect Transistors